

[ABSTRACT]

VALVE DEVICE AND SEMICONDUCTOR PRODUCTION DEVICE

Provided are a valve device and a semiconductor production device that can be used long-term without seizing even during high-temperature use, and which do not have contaminants in the chambers thereof.

The valve device 1 includes: a boosting mechanism 30 that amplifies drive force; a first stem 25 and a second stem 26 that receive force amplified by the boosting mechanism 30 and move; and a diaphragm 11 capable of opening and closing fluid passages 2b, 2c. The boosting mechanism 30 includes: a retainer 31 and bearings 32; shafts 33 having both ends thereof supported by the bearings 32; and arms 34 pivotably supported by the shafts 33 and having an outer end portion 34C that receives drive force and an inner end portion 34B that amplifies and transmits drive force to the first stem 25. In the retainer 31, the bearings 32, the shafts 33, and the arms 34, the bearings 32 and both ends of the shaft 33 constitute a swinging portion in conjunction with the swinging by the arms 34, and thereamong, the bearings 32 include a carbon fiber composite material.

[FIG. 2]